The measurements of doping density in InAs by capacitance-voltage techniques with electrolyte barriers



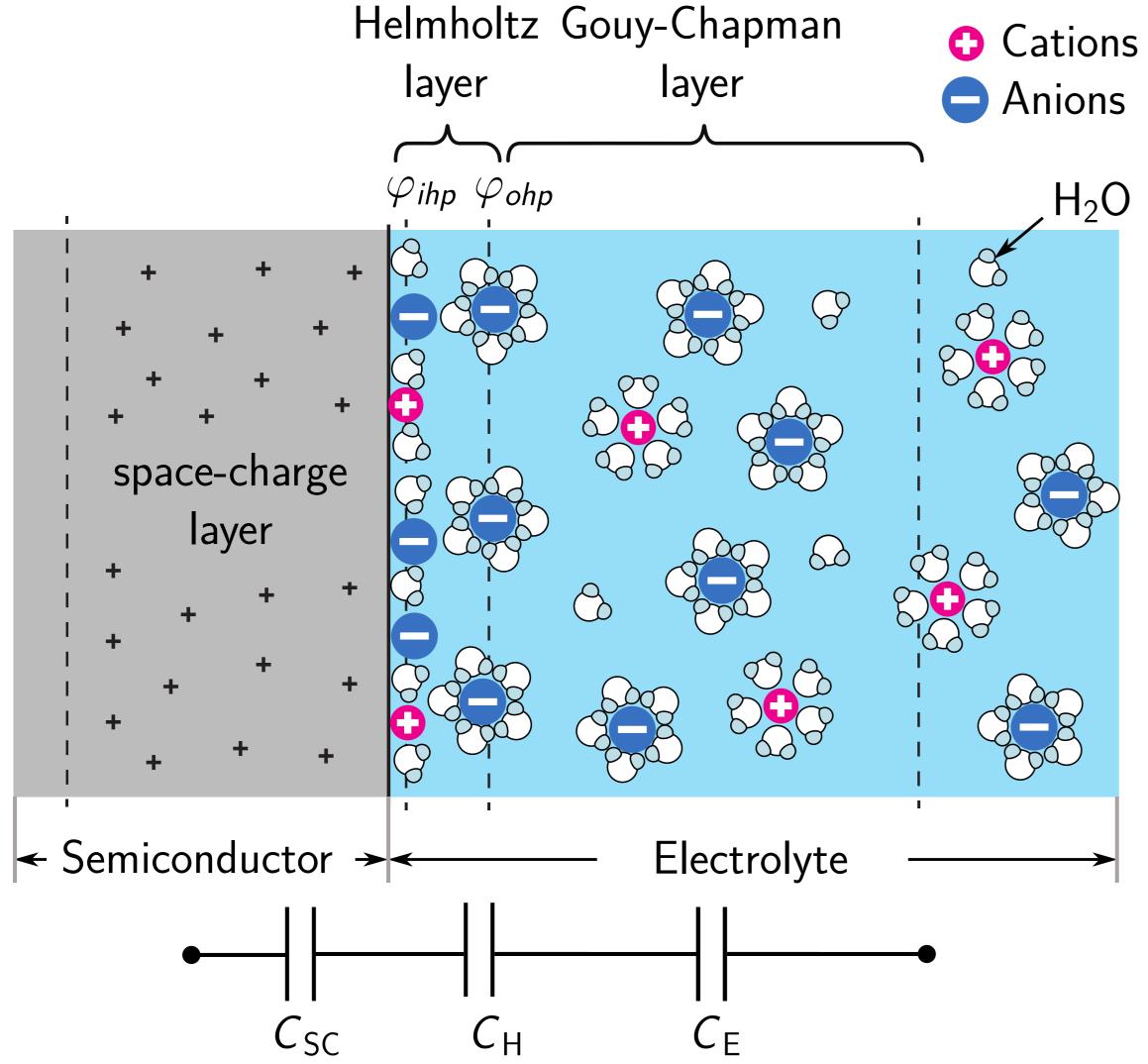
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Motivation

- Schottky contact is usually used in capacitance-voltage characterisation
- Formation of reliable Schottky contact in InAs is difficult due to surface accumulation
- Electrolyte can be used to form Schottky-like barrier
- Using depletion approximation for electrolyte based capacitance-voltage results gives higher concentration compering to Hall measurements

Semiconductor-electrolyte interface



The structure of semiconductor-electrolyte interface

Simulation

Capacitance-voltage characteristics were calculated form potential detributions obtained by solving Poisson equation with modified Thomas-Fermi approximation (MTFA).

Poisson equation

$$\begin{split} \frac{d^2\varphi}{dz^2} &= -\frac{q}{\varepsilon\varepsilon_0} \left[N_D^+ - N_A^- - n(z) + \ p(z)\right] \\ n(z) &= \int_0^\infty \rho_c(z,E) f_{FD}(E) f_{MTFA}(z,E) dE \\ \rho\left(z,E\right) &= \frac{1}{2\pi^2} \left(\frac{2m_\Gamma}{\hbar^2}\right)^{3/2} \sqrt{E} \cdot \sqrt{1+\alpha E} \cdot (1+2\alpha E) \end{split}$$
 where $\alpha = \frac{1}{E_g} \left(1 - \frac{m_\Gamma}{m_0}\right)^2$ — nonparabolicity coefficient

Modified Thomas-Fermi approximation

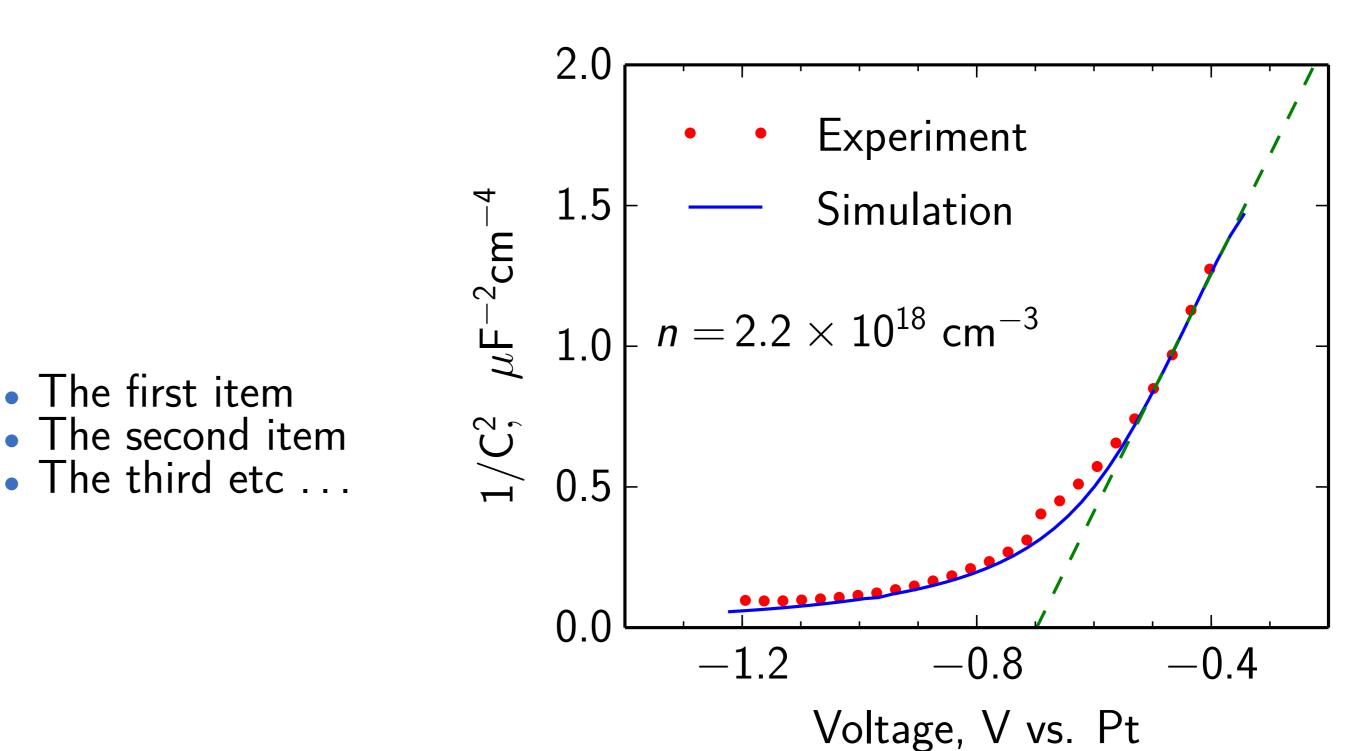
MTFA used to take into account surface accumulation.

$$f_{MTFA}(z, E) = 1 - sinc\left(\frac{2z}{L}\left(\frac{E}{k_BT}\right)^{1/2}(1 + \alpha E)^{1/2}\right)$$

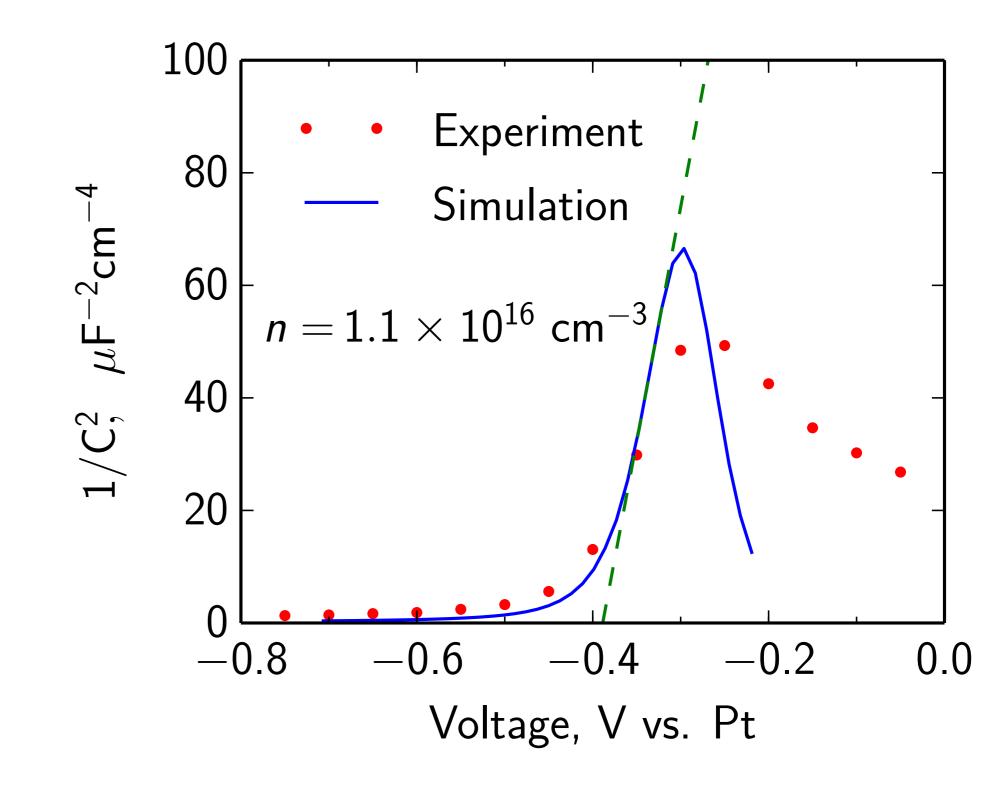
Results

Potential distribution

Mott-Schottky plots of InAs-electrolyte



Mott-Schotky plot of n^+ -InAs



Mott-Schotky plot of epi-InAs

Summary

The first item

The second item

• The third etc . . .